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Kinetics of liquid-assisted densification during flash sintering of ceramic nanoparticles

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Outline

- Densification mechanisms during the Flash Sintering
- Formation of a liquid-film
 - Thermodynamics and Kinetics
 - Densification via liquid-film capillary forces
 - The lack of residual amorphous layer
- Summary & Conclusions

Densification mechanisms suggested for Flash Sintering

Avalanche of point defects 🔶 Liquid film

Bulk phenomenon



Surficial / Interfacial

phenomenon

Densification mechanisms suggested for Flash Sintering



Avalanche of point defects \checkmark Liquid film

Bulk phenomenon



Surficial / Interfacial

phenomenon

The power peak is Artificial



Jha, Lebrun, Raj, <u>J. Eur. Ceram. Soc</u>. **36** (2016) 733

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Flash sintering of dielectric nanoparticles as a percolation phenomenon through a softened film

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(Received 16 February 2017; accepted 3 April 2017; published online 13 April 2017)

Recent work [Biesuz *et al.*, J. Appl. Phys. **120**, 145107 (2016)] showed analogies between the flash sintering and dielectric breakdown in α -aluminas pre-sintered to different densities. Here, we show that flash sintering of dielectric nanoparticles can be described as a universal behavior by the percolation model. The electrical system is composed of particles and their contact point resistances, the latter softened first due to preferred local Joule heating and thermal runaway during the flash. Local softening has a hierarchical and invasive nature and propagates between the electrodes. The flash event signals the percolation threshold by invasive nature of the softened layer at the particle surfaces. Rapid densification is associated with local particle rearrangements due to attractive capillary forces induced by the softened film at the particle contacts. Flash sintering is a critical phenomenon with a self-organizing character. The experimental electric conductivity results from flash sintering are in full agreement with those calculated from the percolation model. *Published by AIP Publishing*. [http://dx.doi.org/10.1063/1.4980853]



FIG. 1. Electric conductivity of α -Al₂O₃ nanoparticles subjected to flash sintering at 1200 °C under 1000 V·cm⁻¹ versus time (top x-axis) (Ref. 10), and the volume fraction of the melt *p* (bottom x-axis). The experimental (red dashed-curve) coincides with the calculated (dotted black-curve) from the percolation model. The flash "incubation time" of 81 s was adjusted to the percolation threshold at $p_c = 0.247$ (open circle).

Invasion Percolation Model via surface softening

- 1. Joule heating at critical particle contacts \rightarrow local melting.
- 2. Incubation time is associated with the percolation threshold.
- 3. Current percolation through the melt.

No current limit: Dielectric breakdown

Current limit: Current control forms local melts throughout

the specimen → Particle wetting and rearrangement by capillary forces.

Chaim, Chevallier, Weibel, Estournes, <u>J. Appl. Phys</u>. **121** (2017) 145103

On thermal runaway and local endothermic/exothermic reactions during flash sintering of ceramic nanoparticles *J Mater Sci* (2018) 53:6378–6389

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Theory

Heat transfer from nanoparticles

Conduction heat transfer

Radiation heat transfer

Heat balance at flash event

Thermodynamics of Liquid-film formation



Chaim, Estournes, <u>J. Mater. Sci.</u> **53** (2016) 6378-89

Thermodynamics of Liquid-film formation



Chaim, Estournes, <u>J. Mater. Sci.</u> **53** (2016) 6378-89

Densification during Flash Sintering by Liquid-film Capillary



Particle diameter [nm]	50	100	200	500	1 µm
Capillary pressure [MPa]	56	28	14	5.6	2.8

Hot Press Values

Regular Article

On the kinetics of liquid-assisted densification during flash sintering of ceramic nanoparticles



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Scripta Materialia 158 (2019) 88–90

Department of Materials Science and Engineering, Technion – Israel Institute of Technology, Haifa 32000, Israel

A R T I C L E I N F O

Article history: Received 15 August 2018 Accepted 16 August 2018 Available online 31 August 2018 Liquid-film assisted Sintering

The capillary force in the presence of liquid is equivalent to

externally applied pressure of:

$$P_{ext} = 2\pi\sqrt{2} \cdot \frac{\gamma_{lv}}{r_p} \cos\theta$$

- γ_{lv} liquid-vapor surface energy
- r_p particle radius
- $\hat{\theta}$ wetting angle

R.B. Heady, J.W. Cahn, Metall Trans 1 (1970) 185-189

Liquid-film Sintering Kinetics

The main question is:

Are the kinetics of these processes fast enough to fulfill a few seconds durations of the flash sintering process.

Therefore, our main target is to evaluate the time scale of the wetting and rearrangement processes using the existing models.

Electro-osmotic / Capillary liquid flow

- We checked the electro-osmotic forces and velocities and capillary forces and velocities.
- For electric fields perpendicular and parallel to the liquid at the contact.
- For jammed particles and free-to-move particles.



Electro-osmotic liquid flow

The terminal velocity, V of the molecule (cation with two anions) in the liquid film at the particle contact subjected to external electric field parallel to the film is:

$$V = \frac{Z \cdot e E}{4\pi a}$$

- *Z* cation valence electrons *e* electron charge
- E electric field
- a average molecule radius
- viscosity of the liquid \boldsymbol{n}

Electro-osmotic liquid flow

The flow speed of the anionic polyhedra under the electric field at the edges of the liquid film and against the drag by the positive ions at the double-layer.

MgO-doped Al_2O_3 @ 1000 V/cm Al_2O_3 melt: Z = 3, a = 0.319 nm



Viscosity of 0.044 [Pa·s] at 2323K

Terminal velocity: 272 μm·s⁻¹

Electro-osmotic liquid flow

- The directional symmetry of the electric field imposes directional flow in the field direction (Posieuille flow).
- If one particle is free of geometrical constraints, the viscous drag may shear it from its neighbor (Couette flow).

Particle rearrangement is accelerated by particle sliding and rotation assisted by the electro-osmotic flow.



Capillary driven liquid flow

- Superposition of the acting forces to highlight the effect of the capillary forces on the flow of the Liquid-film.
- The liquid at the contact leads to capillary forces that are balanced by the viscous drag.
- We assumed that the melt at the contact flows radially between the two particles.

Capillary driven liquid flow

- Following the velocity profile between two fixed and parallel disc surfaces (Posieuille flow).
- The maximum radial flow rate of the liquid due to pressure gradient △P expressed as:

$$u_{max} = \frac{\Delta P \ (\delta_b)^2}{2 \ r \ ln\left(\frac{r_2}{r_1}\right)}$$

- δ_b is the liquid film thickness,
- η is the liquid viscosity

r is the radial distance somewhere between r_1 (disc center) and r_2 (disc perimeter) where the *external* pressure gradient exist

The case of particle neck wetting

- The driving force for wetting is the internal capillary force due to the curvatures at the liquid meniscus.
- The pressure gradient is:

$$\Delta P = \gamma_{l\nu} \left(\frac{1}{r_2} - \frac{2}{\delta_b} \right)$$

- $\gamma_{l\nu}\,$ is the liquid-vapor surface energy
- r_2 is the contact radius

Two curvatures with positive and negative signs

The Maximum flow velocity

The maximum flow velocity at the film perimeter, r₂, is:

$$u_{max} = \gamma_{lv} \left(\frac{1}{r_2} - \frac{2}{\delta}\right) \frac{(\delta_b)^2}{2 r_2 \ln\left(\frac{r_2}{r_1}\right)}$$

The above equations based on the steady state flow conditions. Nevertheless, we are interested in the liquid flow at the early

stages of the wetting hence, our calculations may be estimates.

The Maximum flow velocity

- Example: MgO-doped Al₂O₃
- $r_p = 50 \text{ nm}, \gamma_{lv} = 0.7 \text{ J} \cdot \text{m}^{-2}$
- Liquid film thickness of δ_b = 1.5 nm
- Assuming a dry neck to particle radius ratio 0.02 in the green compact, hence $r_1 = 0.02 \cdot r_p$

Wetted neck to particle radius ratio of 0.10 and 0.20 that correspond to neck radii of 5 nm and 10 nm

Maximum flow velocities of 1.04 m·s⁻¹ and 0.48 m·s⁻¹

The Maximum flow velocity

- These extremely high velocities indicate that liquid flow is instantaneous (i.e. from the time of its formation at the neck center) hence the neck is fully wet and the liquid reaches the neck meniscus within tens of nanoseconds.
- Comparison of the ion velocities in the melt:

Capillary force effect >> Electric field effect

Is there any residual amorphous phase?

- Solidification of the melt by epitaxial (heterogeneous) nucleation
- Most favorable on its counterpart solid substrate.
- The nucleation energy barrier needed for such a critical nucleus:

$$\Delta G_{het}^* = \frac{16 \pi}{3} \frac{(\gamma_{sl})^3}{(\Delta G_v)^2} S(\theta)$$

 γ_{sl} - solid-liquid specific interface energy

 ΔG_{v} - free energy change per unit volume due to the nucleus

S (heta) - nucleus shape factor that depends on the contact angle heta

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S (heta) - nucleus shape factor that depends on the contact angle heta

Sudden & drastic increase in dissipated Power



Furnace Temperature, °C

R. Raj <u>J. Am. Ceram. Soc</u>. 99 (2016) 1400

Conductivity increase vs. furnace temperature



T. Jiang et al. <u>J. Am. Ceram. Soc.</u> 98 (2015) 1717

Numerical model for particle size effects on flash sintering temperature of ionic nanoparticles

Rachman Chaim^{1,*} (D

J Mater Sci (2018) 53:13853–13864

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Figure 6 Calculated flash temperature versus particle radius and neck to particle radius ratio in 3YSZ in the particle size range of 50–2000 nm.

Effects of the fundamental oxide properties on the electric field-flash temperature during flash sintering

Rachman Chaim^{a,*}, Claude Estournès^b

Scripta Materialia 163 (2019) 130–132

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Fig. 1. Experimental flash temperature–electric field relations in different oxides: Al₂O₃ [1], BaTiO₃ [10], Ce_{0.9}Gd_{0.1}O_{1.95} [11,12], Ce_{0.8}Gd_{0.2}O_{1.90} [13], (La_{0.6}Sr_{0.4}) (Co_{0.2}Fe_{0.8}) O₃ [12], MgTiO₃ [16], MnCo₂O₄ [17], Pb(Zr_{0.52}Ti_{0.48}) O₃ – PZT [18], SrTiO₃ [20], TiO₂ [21], Y₂O₃ [22], 3YSZ [23], 8YSZ [24], and ZnO [25].



the 'structure-field maps' of Goldschmidt

Chaim, Estournes, Scripta Mater **163** (2019) 130-132



Fig. 3. Fusion entropy–flash temperature diagram of oxides normalized for the 100 nm particle size under the 500 V \cdot cm⁻¹ electric field. The lines used as guidelines only to highlight the oxides with similar crystal structure.

Chaim, Estournes, Scripta Mater **163** (2019) 130-132

Summary & Conclusions

- The kinetics of flash sintering assisted by a liquid-film is in agreement with the experimental time scales of a few seconds.
- Joule heat provides the activation energy for local surface softening / melting.
- Thermal runaway is an endothermic local melting of the particle contacts. The transient liquid solidifies after the particle rearrangement.

Summary & Conclusions

Homologous crystallization of the local melt after particle rearrangement is energetically preferred due to the exothermic nature of solidification.

Thank you for your attention

